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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Mark Henry SHIPTON et al.

Group Art Unit: 1775

Application No.: 10/676,042

Examiner: A. AUSTIN

Filed: October 2, 2003

Docket No.: 117313

For: METHOD OF FORMING A DIFFUSION BARRIER ON A METALLIC SUBSTRATE

REQUEST FOR RECONSIDERATION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In reply to the June 5, 2006 Office Action, reconsideration of the rejection is respectfully requested in light of the following remarks. Claims 1-7 and 15-18 are pending in this application.

The Office Action rejects claims 1-7 and 15-18 under 35 U.S.C. §103(a) over Deakin (WO 94/18359) in view of Sangeeta (U.S. Patent No. 6,395,406). The rejection is respectfully traversed.

In particular, none of the applied references, alone or in combination, disclose or suggest a method of forming a platinum aluminide diffusion barrier on a titanium alloy substrate that includes applying to the substrate a coating comprising particulate platinum and particulate aluminum in an organic carrier, and performing a reaction treatment in a range of about 200°C to about 600°C, as recited in independent claim 1.

Deakin teaches forming a platinum aluminide layer on a titanium substrate by sequential definition of a platinum layer followed by an aluminum layer (Abstract). In fact, a